



DPW

PATENT  
YOR920040022 IBM-272

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of : Matthew Colburn, et al.

Serial Number : 10/799,282

Filing Date : March 13, 2004

Examiner : John A. McPherson

Group Art Unit : 1756

For : Method for Fabricating Dual Damascene Structures  
Using Photo-Imprint Lithography, Methods for  
Fabricating Imprint Lithography Molds for Dual  
Damascene Structures, Materials for Imprintable  
Dielectrics and Equipment for Photo-Imprint  
Lithography Used in Dual Damascene Patterning.

TO: The Honorable Commissioner of Patents  
and Trademarks  
Post Office Box 1450  
Alexandria, VA 22313-1450

In response to the Requirement for Restriction Official Action dated April 4, 2007,  
Applicants hereby elect Group 1 which relates to a multilevel mold embodied in Claims 1, 13,  
51 - 57 and 60. The subject matter is classified in Class 249, subclass 115.

The remaining claims are hereby cancelled.

Please address all future correspondence in this matter to the undersigned at 6136 West  
Kimberly Way, Glendale, AZ 85308.

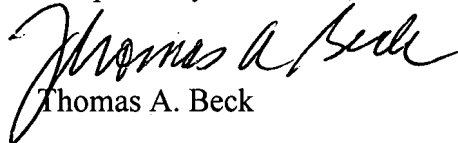
07/10/2007 KGBREH1 03200100 021651 10759282  
01 FC:1251 120.22 DA

Appln/Control No. 10/799,282

03/13/2004 Colburn, et al.

The Commissioner is requested to grant a one month extension of time within which to respond to the above-noted Official Action. Please charge Deposit Account 02-1 651 in the amount of \$120.00 to cover the one month extension fee. A duplicate copy of this page is enclosed.

Respectfully Submitted,



Thomas A. Beck

Registration No. 20,816

6136 West Kimberly Way

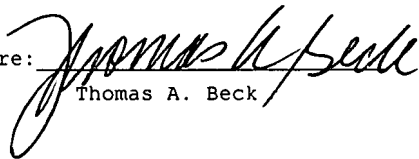
Glendale, AZ 85308

Telephone (623) 466-0080

I hereby certify that this paper is being transmitted by First Class mail addressed to Commissioner of Patents & Trademarks, Post Office Box 1450, Alexandria, VA 22313-1450.

Signature:

Name:

  
Thomas A. Beck

Date: June 30, 2007